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[54] **METHOD FOR REMOVING PHOTORESIST COMPOSITION FROM SUBSTRATE SURFACES**

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Related U.S. Application Data

[62] Division of Ser. No. 33,076, Mar. 10, 1993, Pat. No. 5,426,017, which is a continuation of Ser. No. 531,214, May 31, 1990, abandoned.

[51] **Int. Cl.⁶** **G03F 7/16**

[52] **U.S. Cl.** **430/169; 430/189; 430/270.14; 430/331**

[58] **Field of Search** **430/325, 331, 430/270, 168, 189, 169**

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[57] **ABSTRACT**

Ternary mixtures of C₄ to C₈ alkyl acetate, C₄ to C₈ alkyl alcohol, and water, formulated to have a flash point of above 100° F., are disclosed, particularly for use in edge residue removal processes in the fabrication of integrated circuits and like products.

8 Claims, No Drawings